

METHOD AND APPARATUS FOR PREVENTING ARCING AT PORTS EXPOSED TO A PLASMA IN PLASMA PROCESSING CHAMBERS

ABSTRACT

A method and apparatus for preventing arcing at a port exposed to a plasma in a plasma chamber use circuit components causing a door sealing the port to provide a short circuit path at excitation frequency of the plasma. In one embodiment, the door is a slit valve door sealing a substrate transfer port of an etch chamber.

(Fig. 2B)